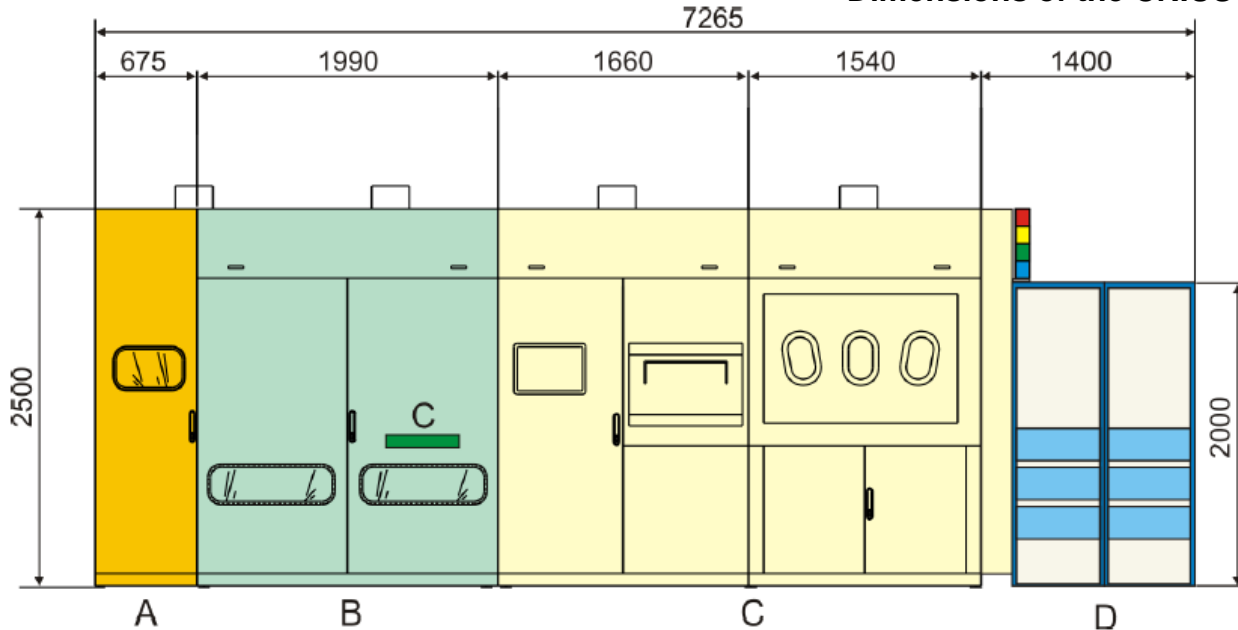


前瞻異質材料金屬有機化學氣相沉積系統 — III-V MOCVD

Model: AIXTRON CRIUS

Dimensions of the CRIUS [mm]



- A** Electrical cabinet
- B** Gas mixing cabinet
- C** Reactor cabinet
- D** Heater power supply unit

Process gases:

H₂

AsH₃ (Arsine)

TMGa (Trimethylgallium)

TMAI (Trimethylaluminum)

TMIIn (Trimethylindium)

DEZn (Diethylzinc)

Si₂H₆ (Disilane, 200 ppm in H₂)